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	FSI0041/US/3	10/628,598
	<b>Applicant</b>	
	Daggett et al.	
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## U.S. PATENT DOCUMENTS

## FOREIGN PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS						
Name	Document Number	Date	Country	Class	Subclass	Translation Yes/No
✓	3-178123	08/1991	Japan			Abstract
	4-94525	03/1992	Japan			Abstract
✓	05-144721	06/1993	Japan			Abstract

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

	Uchiyama, Photoresist Application Device, JP 5-144721 (English Translation), June 1993, pp. 1-10
	Gürer, et al. "Model-based adaptive process control: A CD-control example," Solid State Technology, pp. 205-206, 208, 210, 212 (July 1996)
	Gürer, et al., "...Adaptive Process Control in Lithography," Semicon Korea 98, Semicon Korea Technical Symposium 98, Process & Evaluation Technology I, II, pp. 205-218

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Date Considered: 5/06